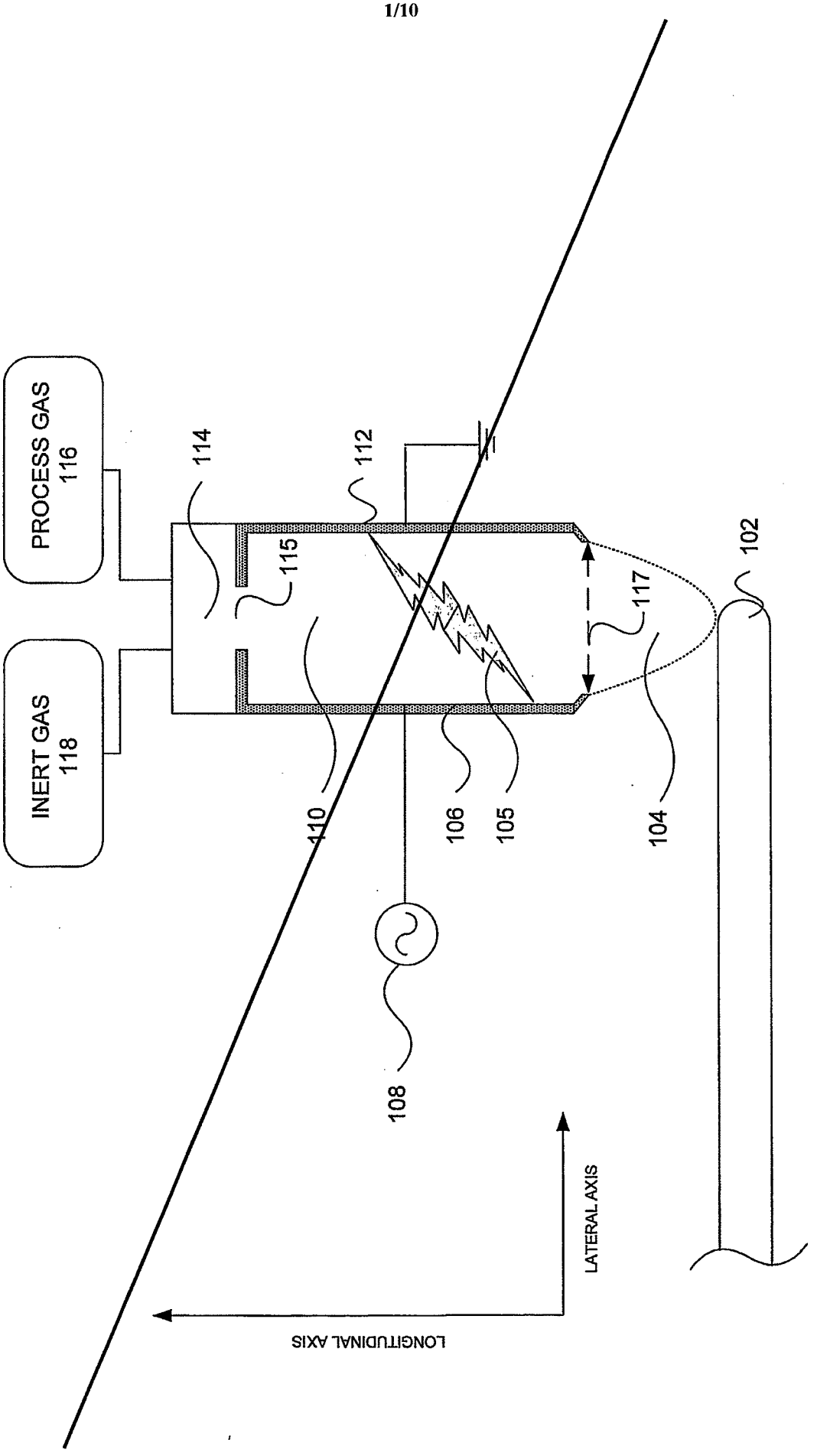

PROCESS GAS
116
INERT GAS
118
114
112
115
117
102
110
106
105
104
108
LONGITUDINAL AXIS
LATERAL AXIS

FIG. 1

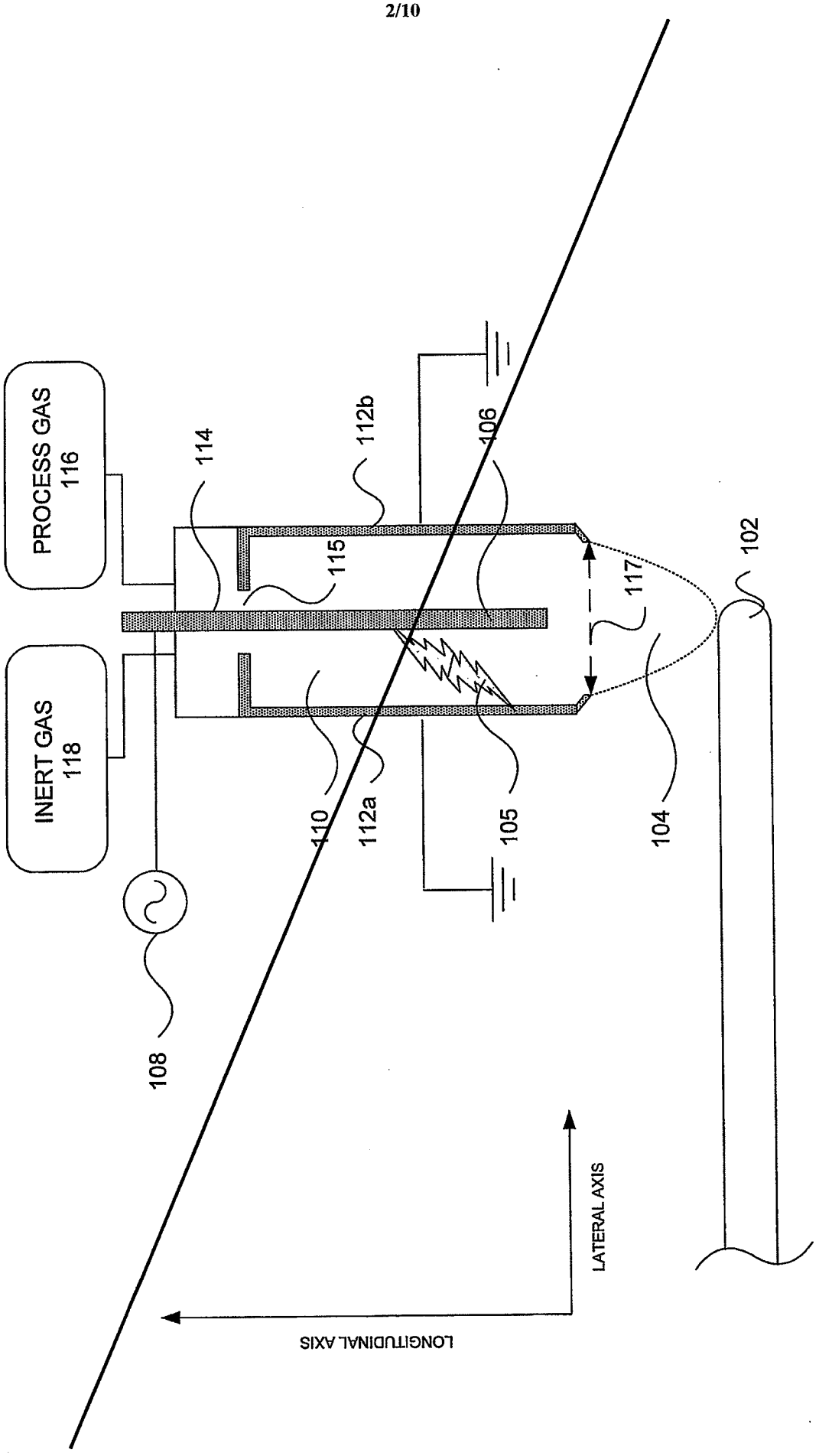

PROCESS GAS
116
INERT GAS
118
108
114
112b
106
115
117
102
110
112a
105
104
LONGITUDINAL AXIS
LATERAL AXIS

FIG. 2

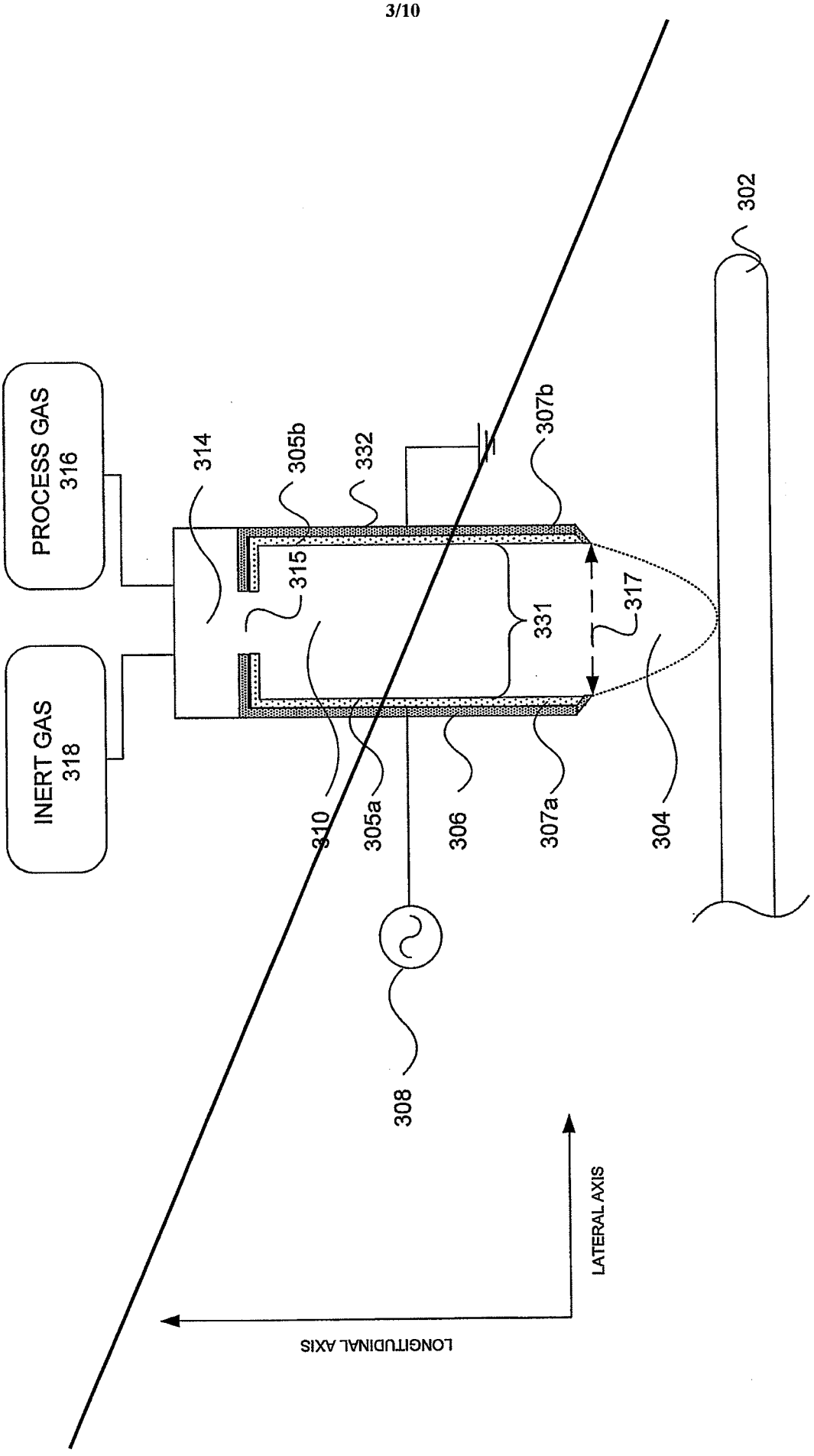

PROCESS GAS
316
INERT GAS
318
314
305b
332
307b
315
331
317
302
310
305a
306
307a
304
308
LONGITUDINAL AXIS
LATERAL AXIS

FIG. 3

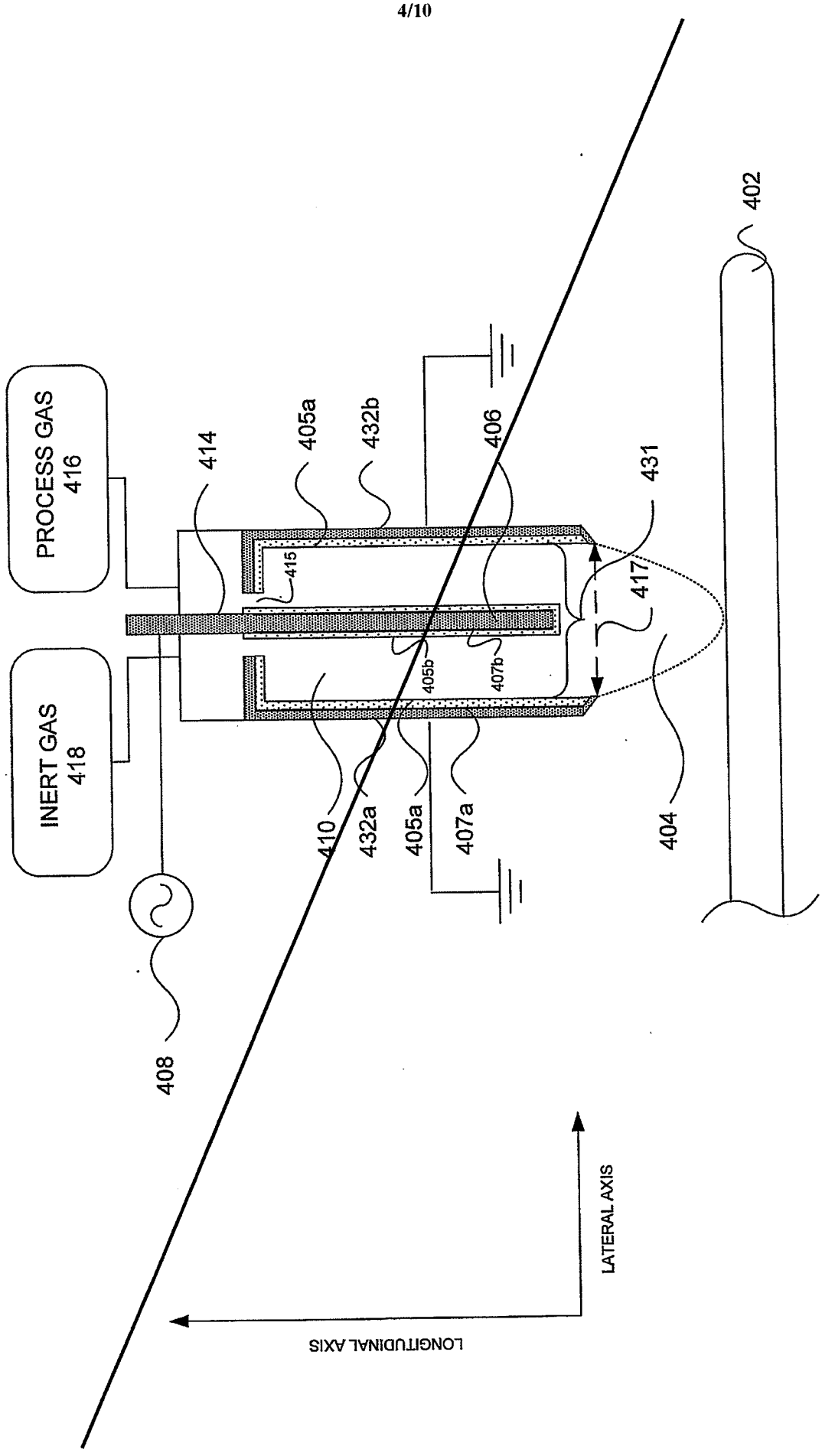

PROCESS GAS
416
INERT GAS
418
408
414
405a
432b
406
431
415
417
405b
407b
410
432a
405a
407a
404
402
LONGITUDINAL AXIS
LATERAL AXIS

FIG. 4

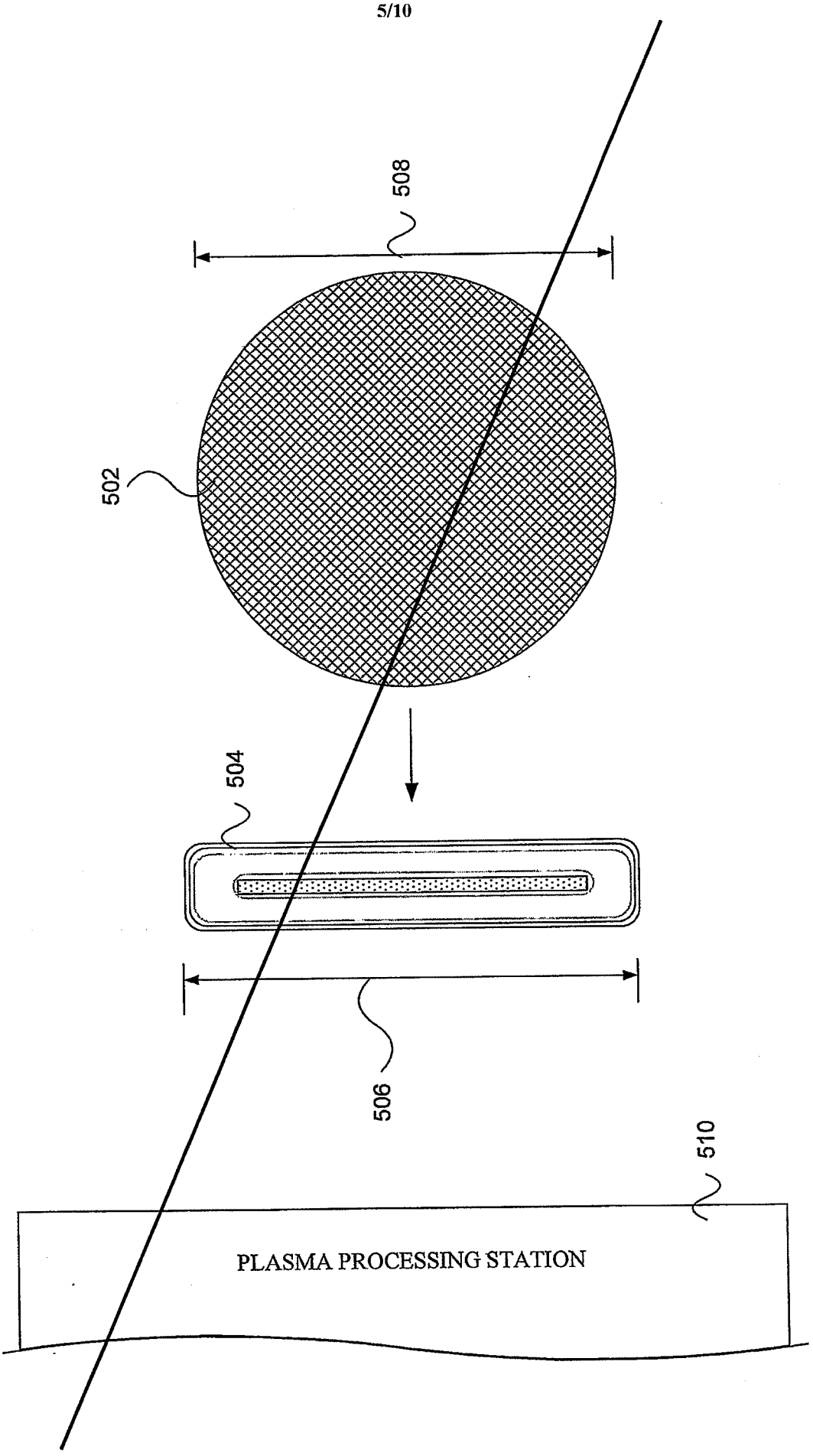


FIG. 5

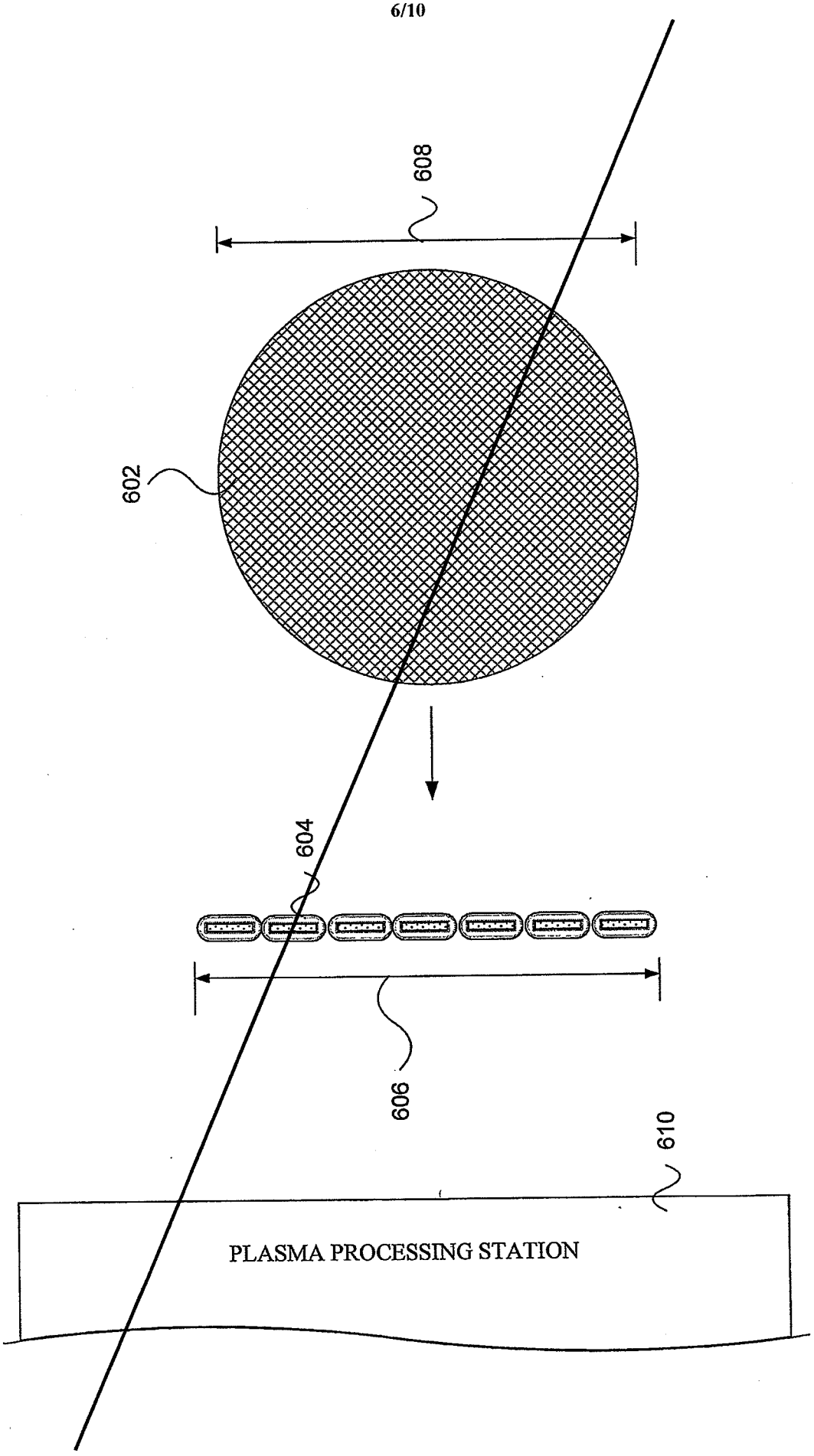


FIG. 6A

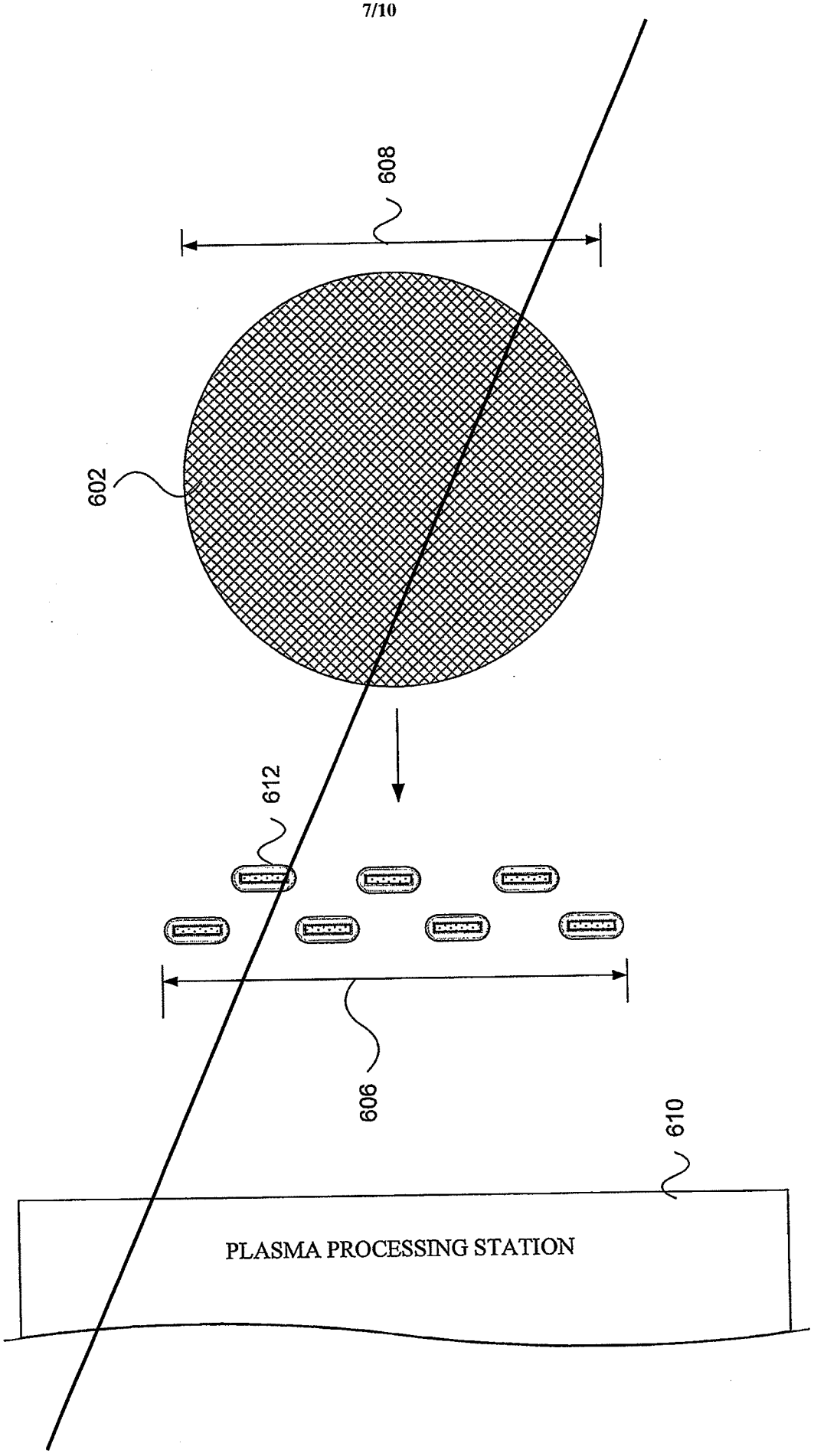


FIG. 6B

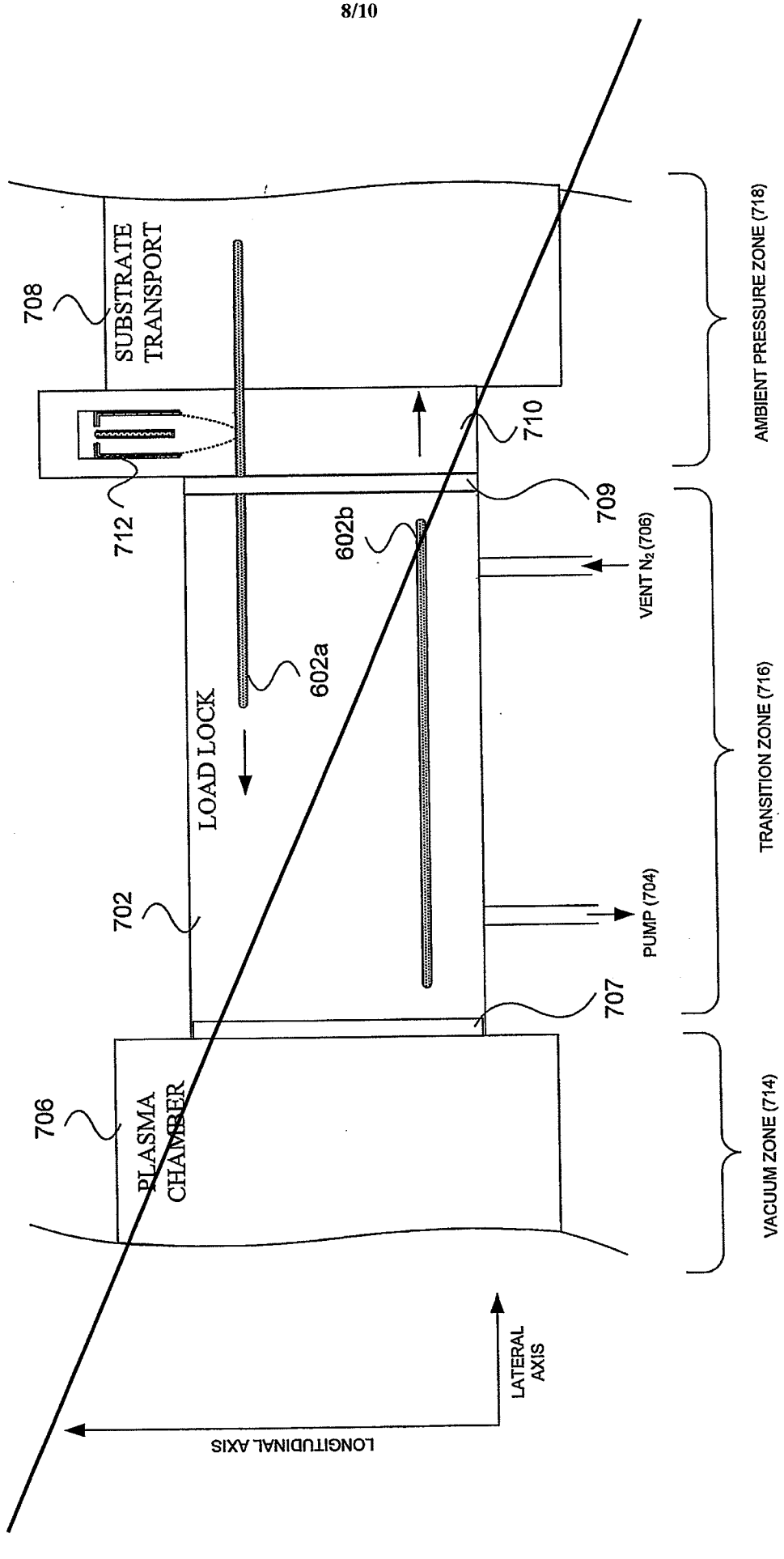

708
SUBSTRATE TRANSPORT
712
710
709
602b
602a
VENT N_2 (706)
LOAD LOCK
702
PUMP (704)
707
706
PLASMA CHAMBER
AMBIENT PRESSURE ZONE (718)
TRANSITION ZONE (716)
VACUUM ZONE (714)
LATERAL AXIS
LONGITUDINAL AXIS

FIG. 7

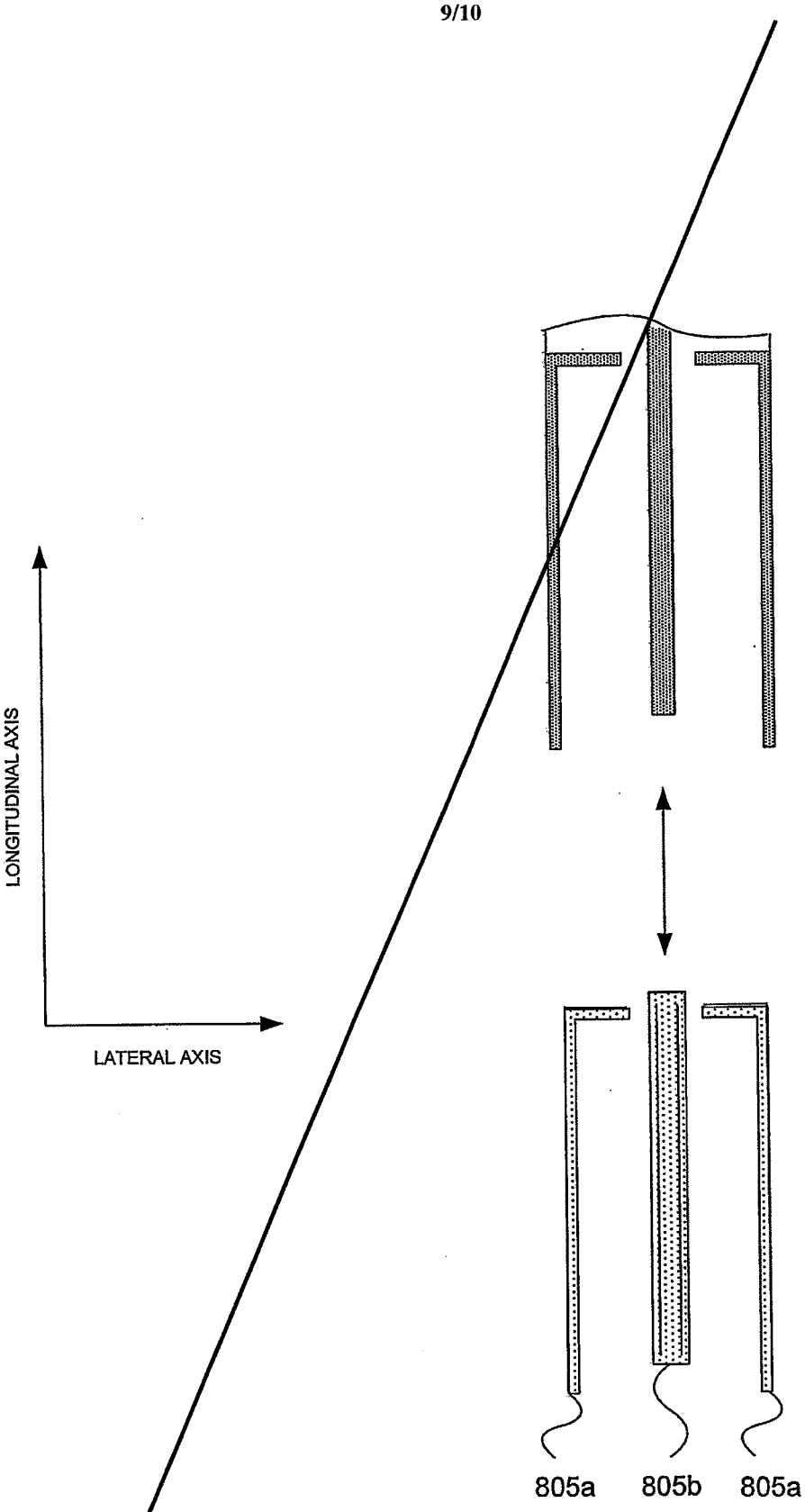


FIG. 8

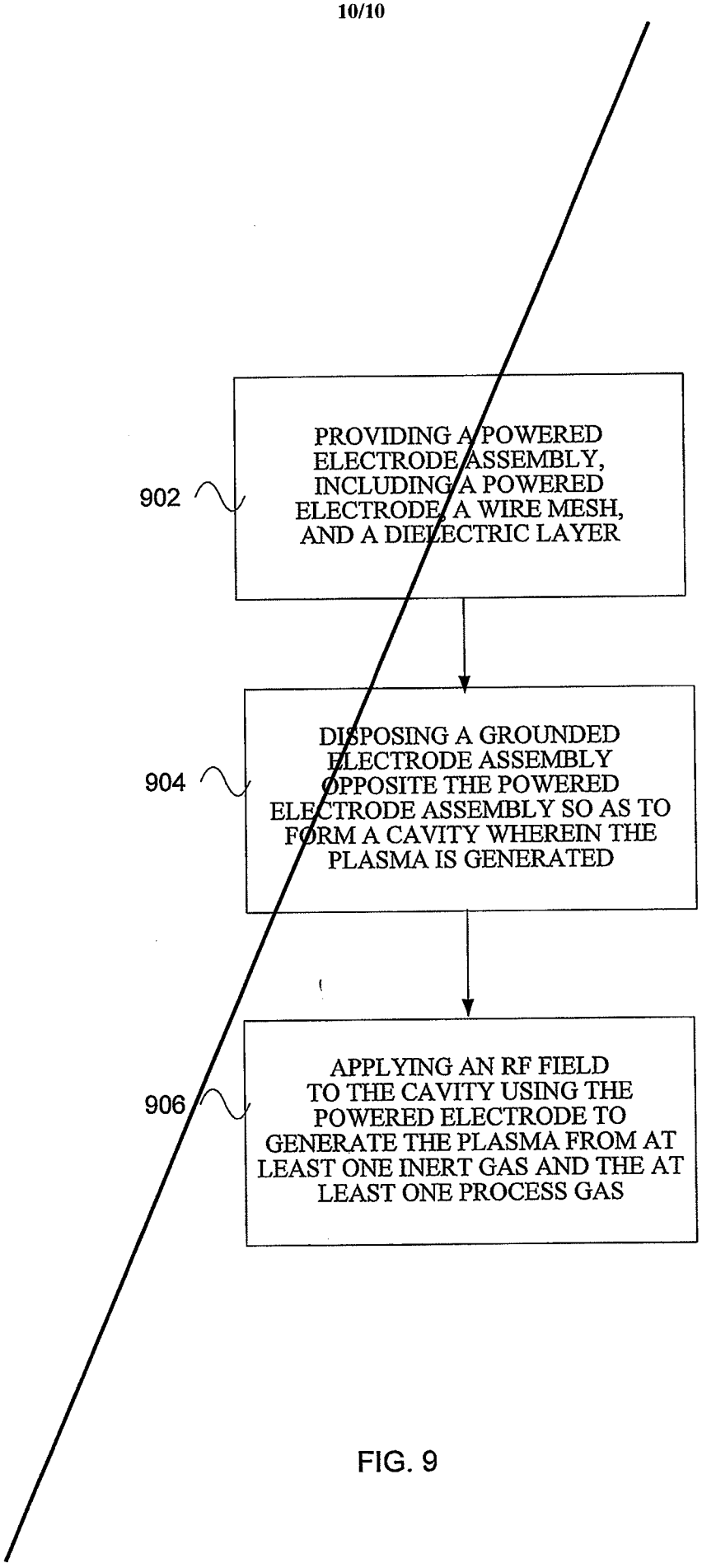

902
PROVIDING A POWERED ELECTRODE ASSEMBLY, INCLUDING A POWERED ELECTRODE, A WIRE MESH, AND A DIELECTRIC LAYER
904
DISPOSING A GROUNDED ELECTRODE ASSEMBLY OPPOSITE THE POWERED ELECTRODE ASSEMBLY SO AS TO FORM A CAVITY WHEREIN THE PLASMA IS GENERATED
906
APPLYING AN RF FIELD TO THE CAVITY USING THE POWERED ELECTRODE TO GENERATE THE PLASMA FROM AT LEAST ONE INERT GAS AND THE AT LEAST ONE PROCESS GAS

FIG. 9

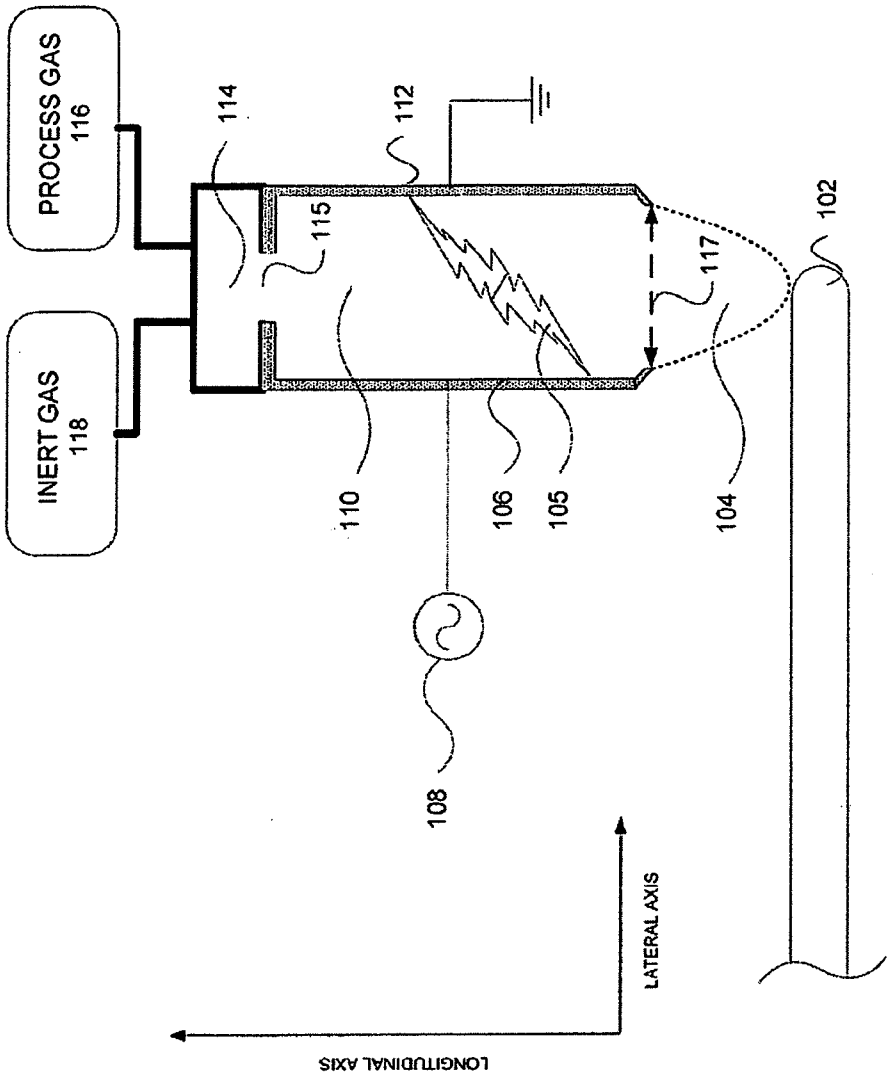


FIG. 1 (Prior Art)

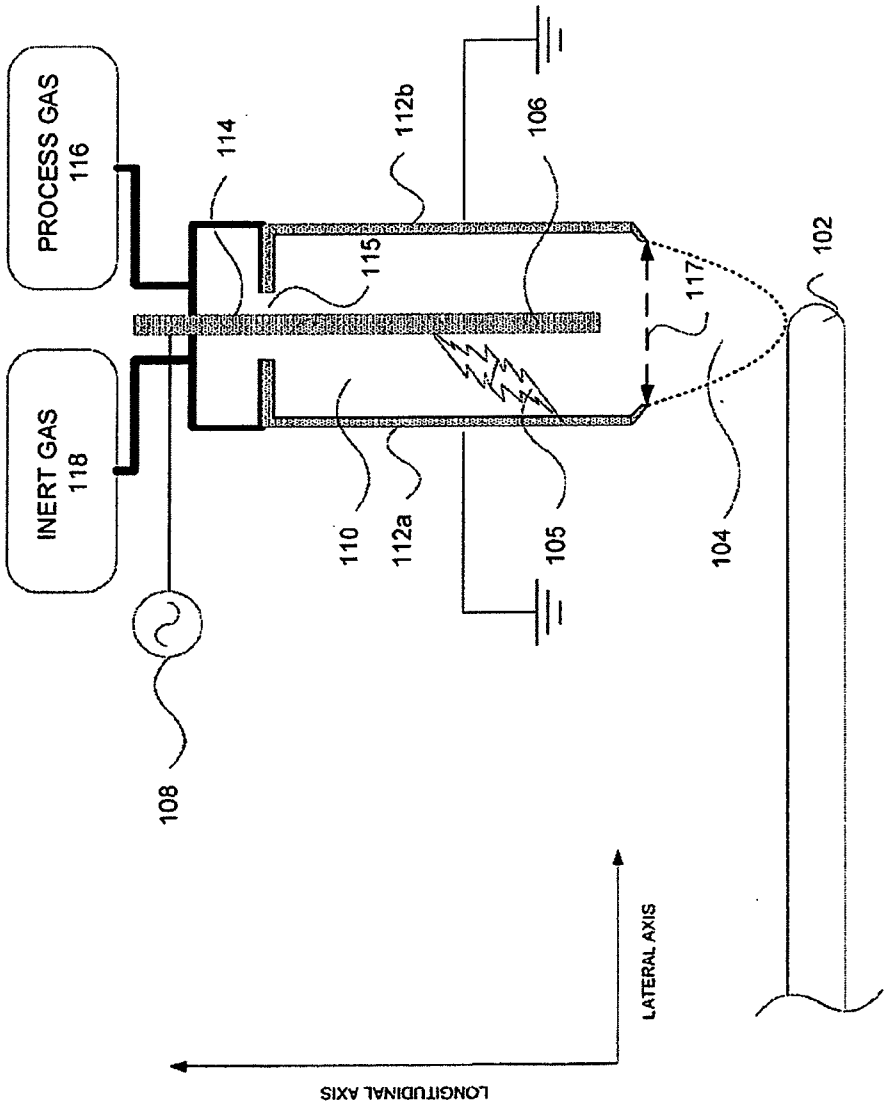


FIG. 2 (Prior Art)

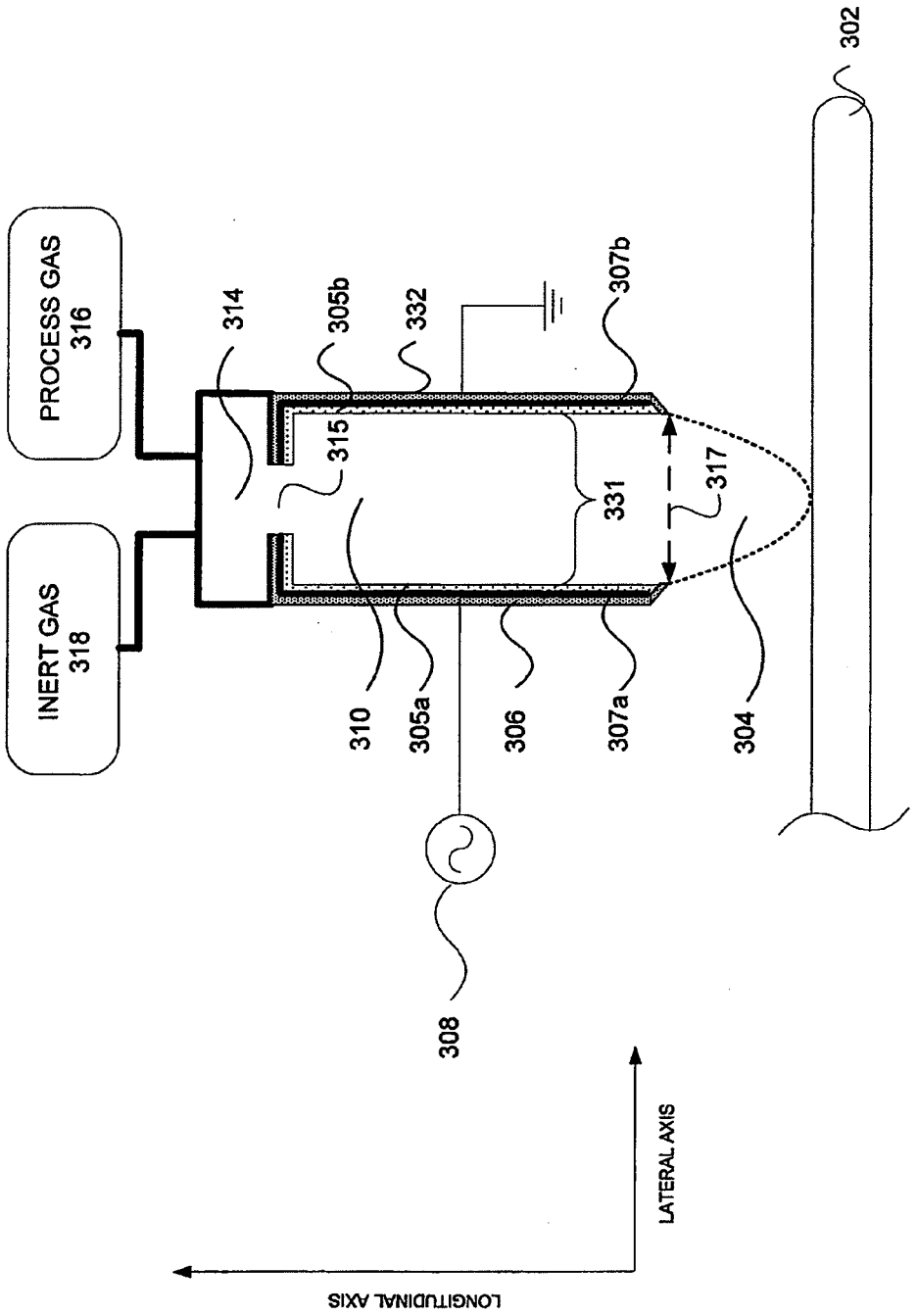

PROCESS GAS
316
INERT GAS
318
314
305b
332
307b
315
331
317
302
310
305a
306
307a
304
308
LONGITUDINAL AXIS
LATERAL AXIS

FIG. 3

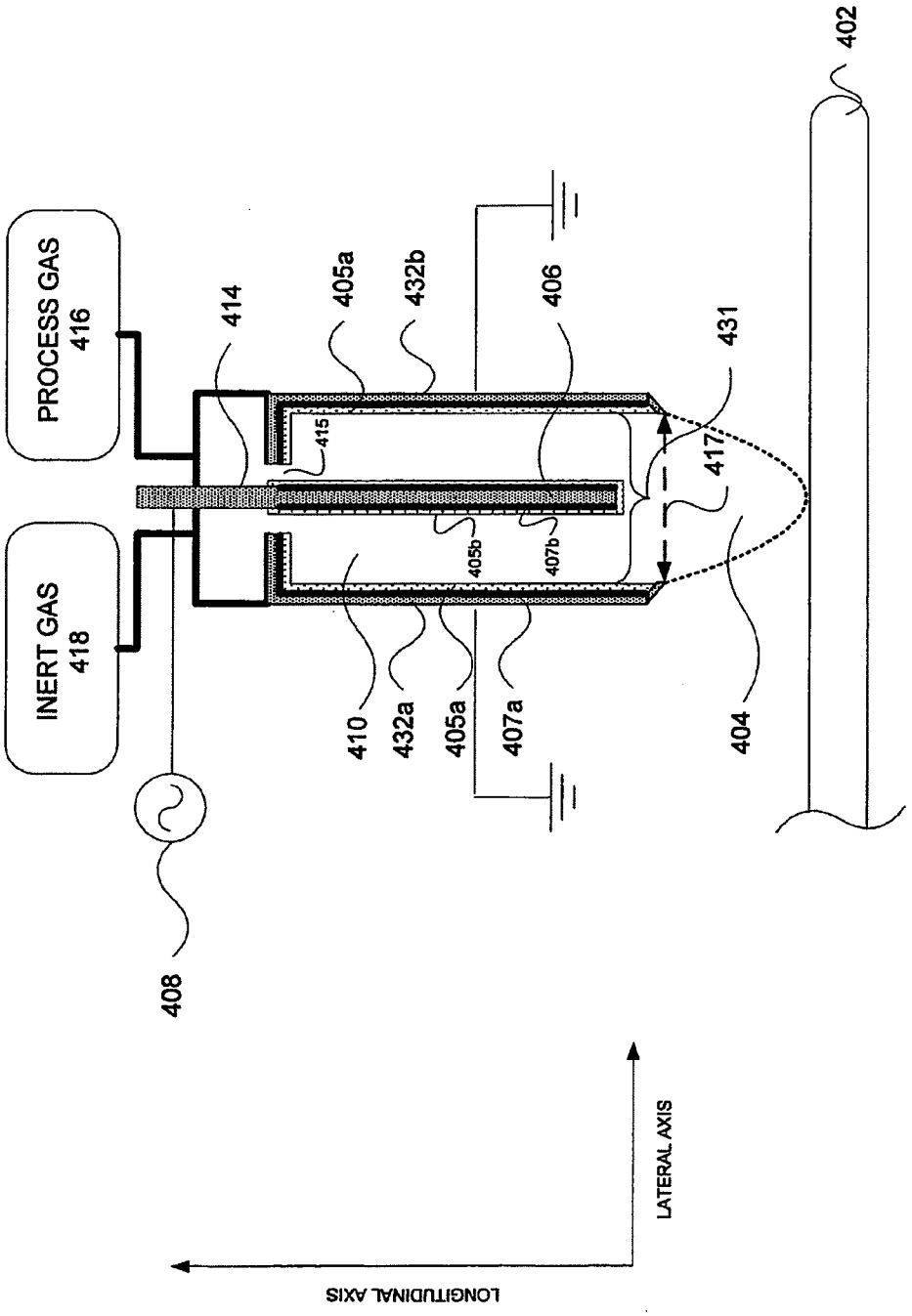

PROCESS GAS
416
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405a
432b
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431
417
402
405b
407b
410
432a
405a
407a
404
LONGITUDINAL AXIS
LATERAL AXIS

FIG. 4

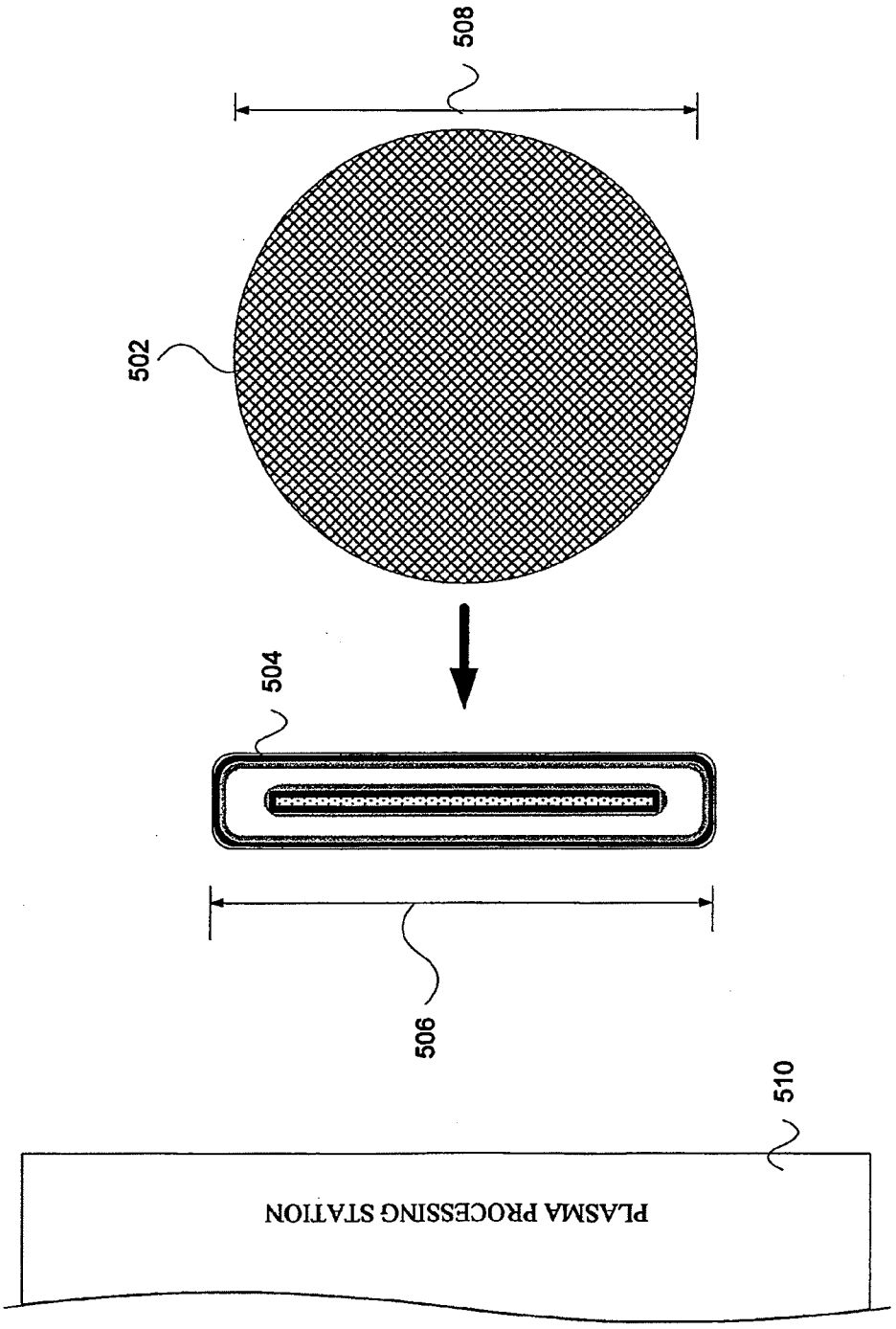


FIG. 5

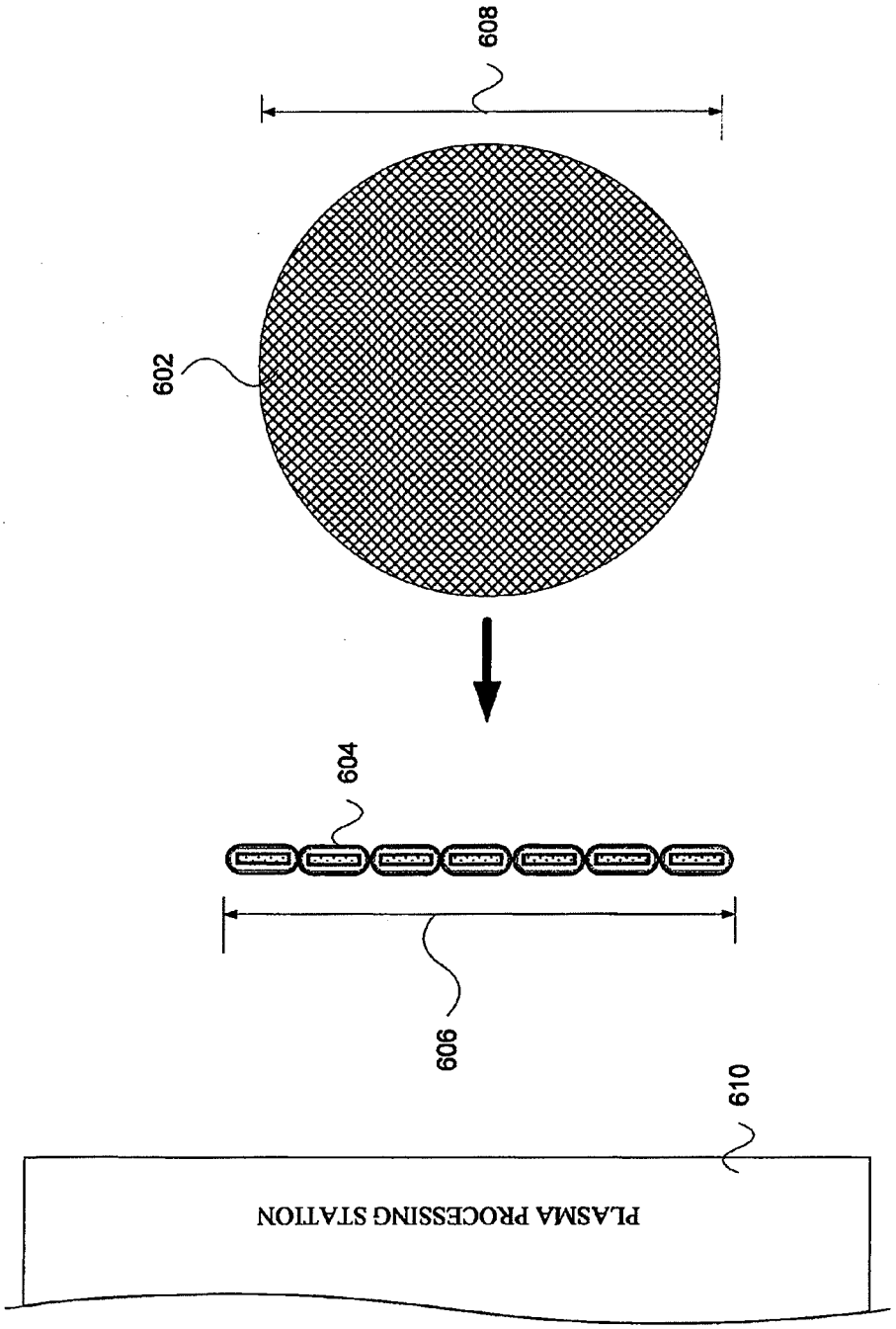


FIG. 6A

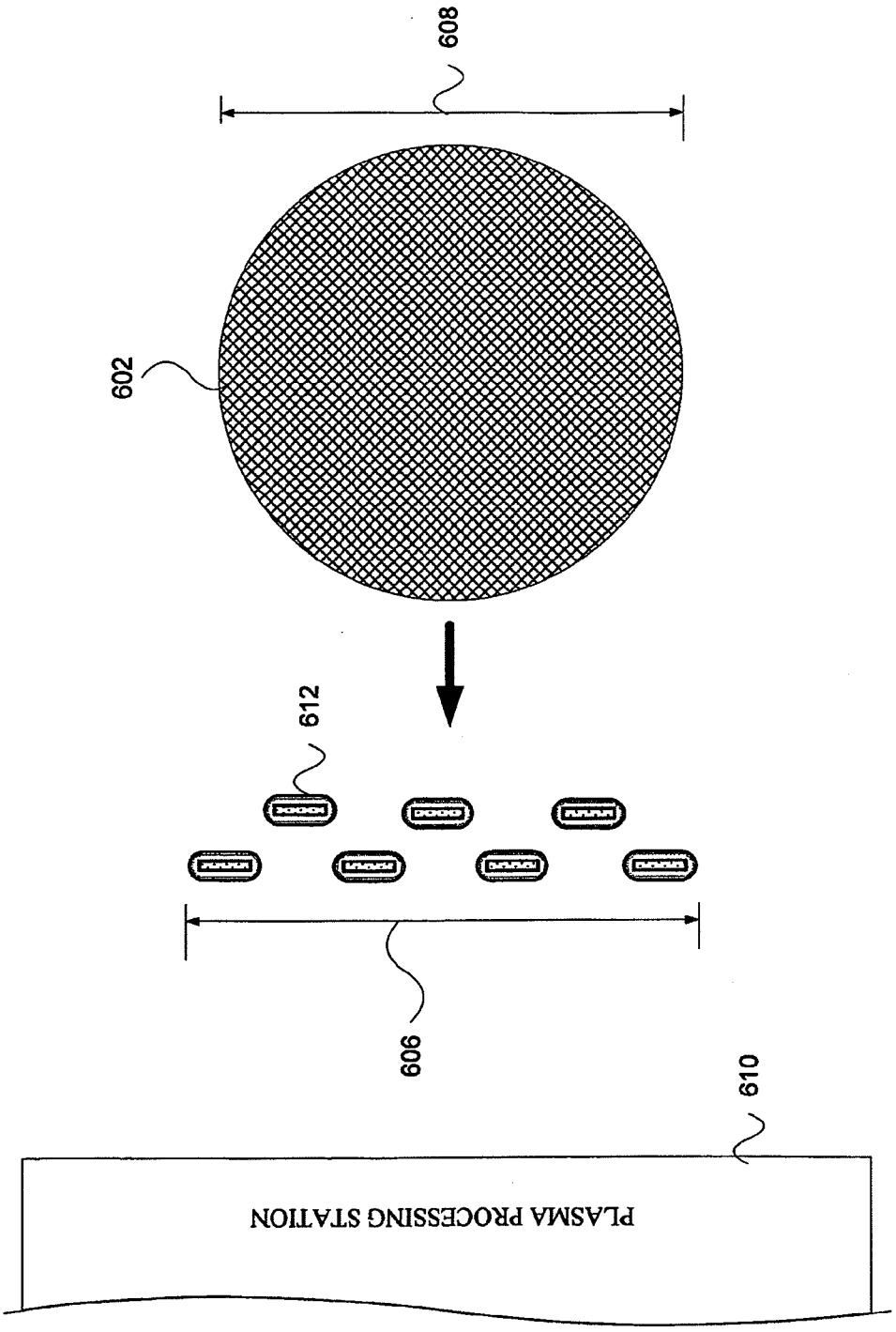


FIG. 6B

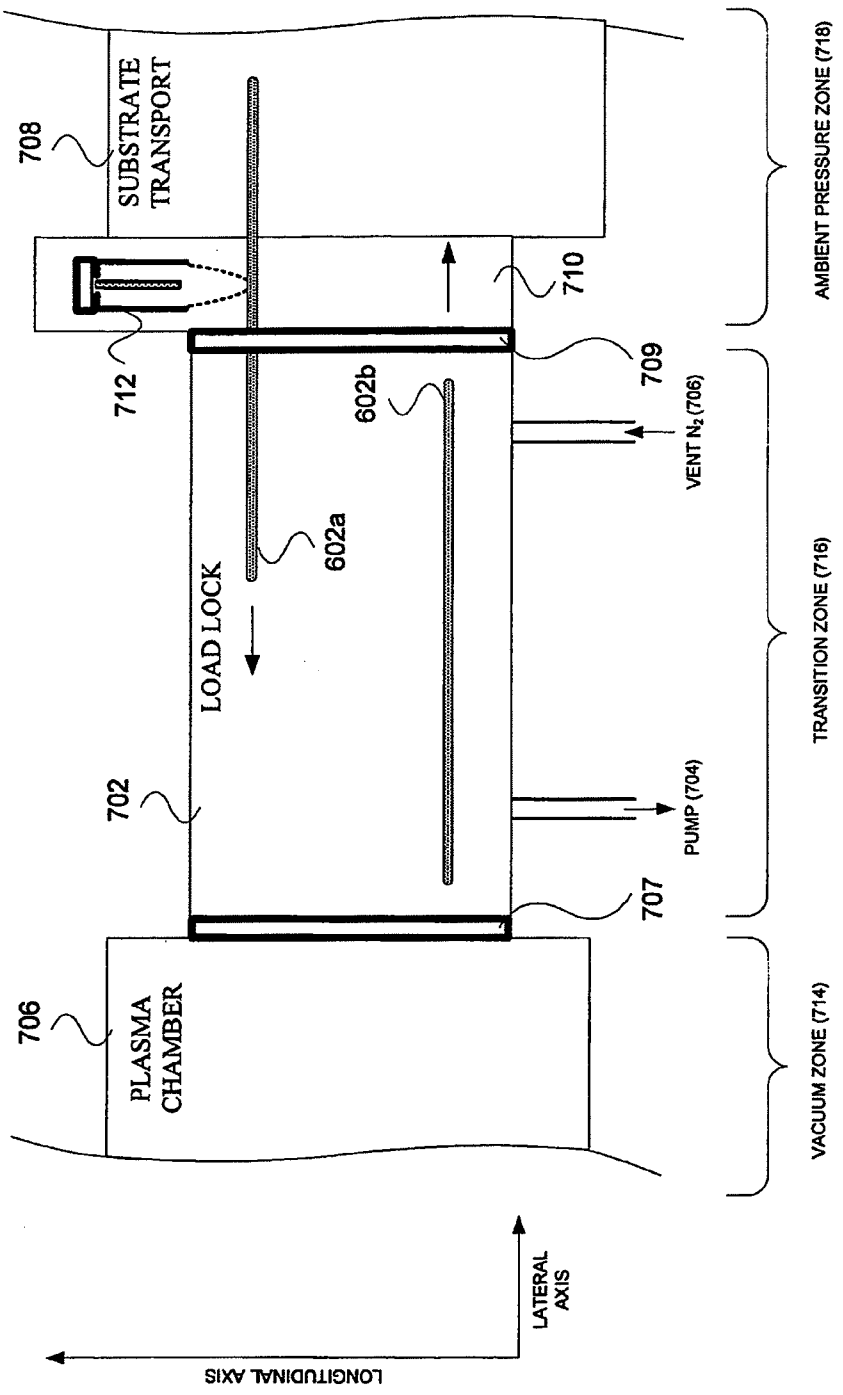

708
SUBSTRATE TRANSPORT
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602a
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706
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TRANSITION ZONE (716)
VACUUM ZONE (714)
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LONGITUDINAL AXIS

FIG. 7

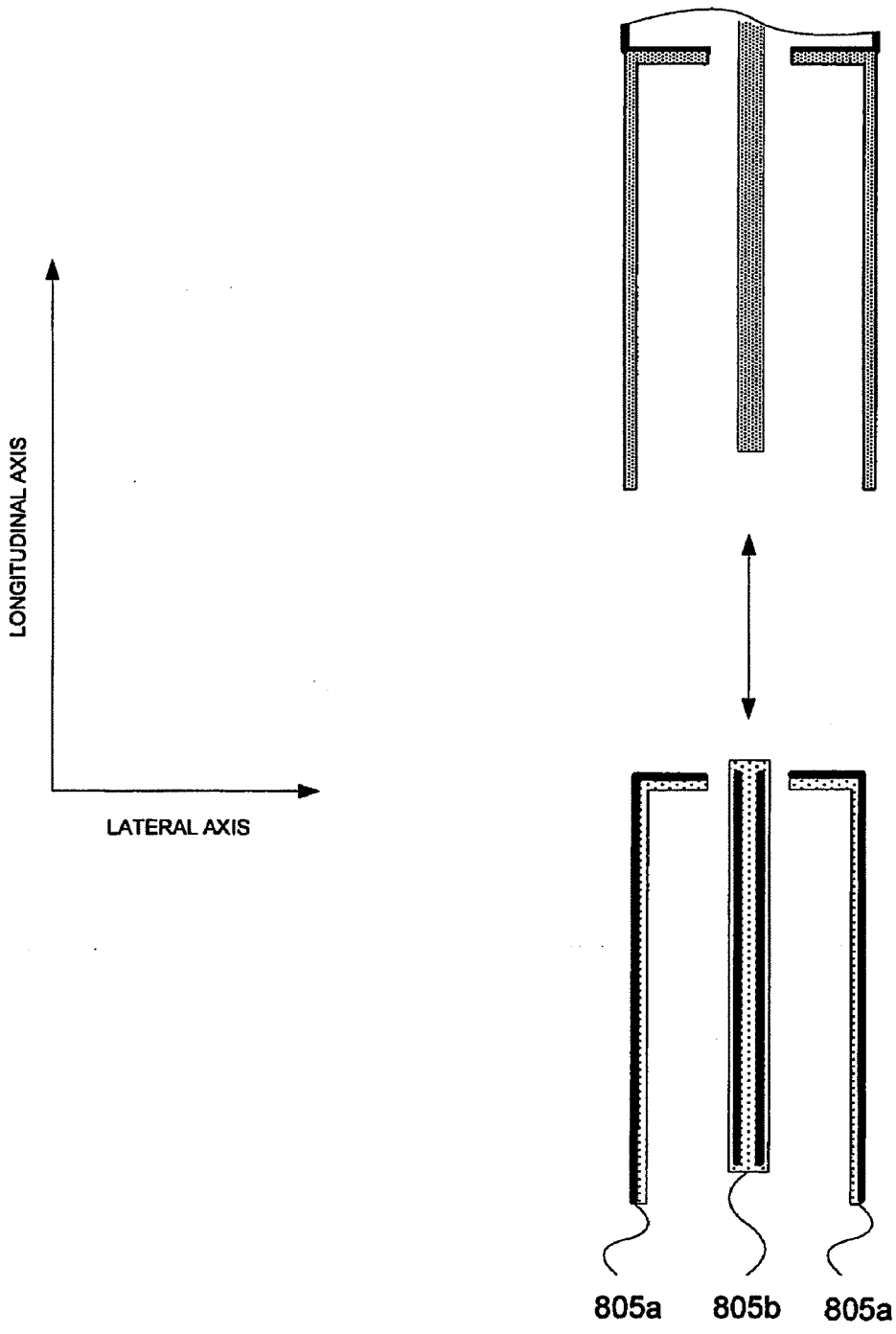


FIG. 8

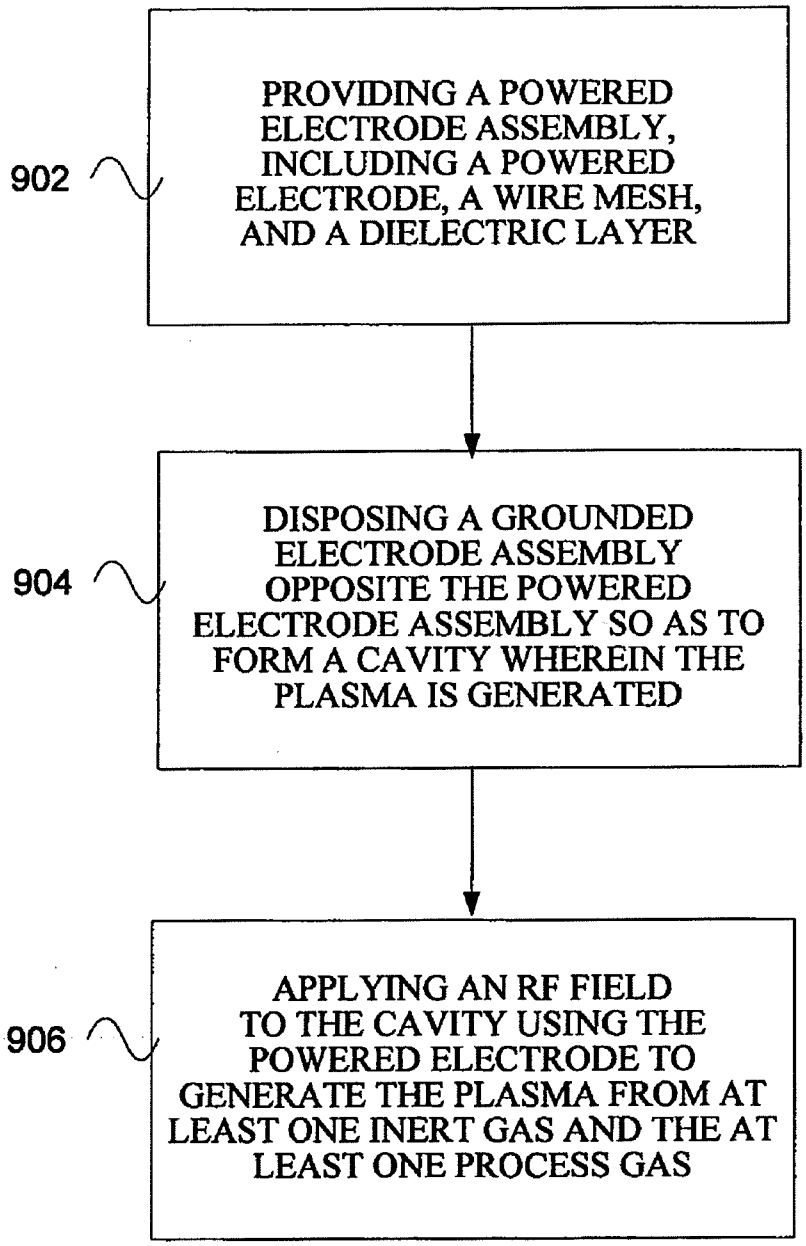

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